Measurement of spin-diffusion length in sputtered Ni films$^1$

CHARLES MOREAU, Albion College, WILLIAM PRATT, Michigan State University, NORMAN BIRGE, Michigan State University — The spin-diffusion length of the electron represents a fundamental transport parameter and plays a central role in the development of spintronic devices. While several measurements of the spin-diffusion length in normal metals and in ferromagnetic alloys exist, measurements in elemental ferromagnets (Ni, Fe, Co) have been scarce. We present a novel sample geometry using giant magnetoresistance (GMR) for the measurement of the spin-diffusion length in elemental ferromagnets with weak scattering asymmetry. We report the first measurement of the spin-diffusion length of Ni using an exchanged-biased Permalloy-based spin-valve, Py/Ni/Cu/Py, where the Ni layer acts as a GMR spoiler layer when its thickness becomes greater than the spin-diffusion length in Ni.

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